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**Citation:** Kim, H., Lee, S., Shin, J. et al. Graphene nanopattern as a universal epitaxy platform for single-crystal membrane production and defect reduction. Nat. Nanotechnol. 17, 1054–1059 (2022).

**As Published:** 10.1038/s41565-022-01200-6

**Publisher:** Springer Science and Business Media LLC

**Persistent URL:** https://hdl.handle.net/1721.1/153569

**Version:** Author's final manuscript: final author's manuscript post peer review, without publisher's formatting or copy editing

# Graphene nanopattern as a universal epitaxy platform for single-crystal membrane production and defect reduction

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**Heterogeneous integration of single-crystal materials offers great opportunities for advanced device platforms and functional systems[1]. Although substantial efforts have been made to co-integrate active device layers by heteroepitaxy, the mismatch in lattice polarity and lattice constants has been limiting the quality of the grown materials[2]. Layer transfer methods as an alternative approach, on the other hand, suffer from the limited availability of transferrable materials and transfer process-related obstacles[3]. Here, we introduce graphene nanopatterns as an advanced heterointegration platform that allows the creation of a broad spectrum of freestanding single-crystalline membranes with substantially reduced defects, ranging from non-polar materials to polar materials and from low-bandgap to high-bandgap semiconductors. Additionally, we unveil unique mechanisms to substantially reduce crystallographic defects such as misfit dislocations, threading dislocations, and antiphase boundaries in lattice- and polarity-mismatched heteroepitaxial systems, owing to the flexibility and chemical inertness of graphene nanopatterns. More importantly, we develop a comprehensive mechanics theory to precisely guide cracks through the graphene layer, and demonstrate successful exfoliation of any epitaxial overlayers grown on the graphene nanopatterns. Thus, this approach has the potential to revolutionize heterogeneous integration of dissimilar materials by widening the choice of materials and offering flexibility in designing heterointegrated systems.**

With the advancement of current electronic and photonic devices, demands for heterogeneous integration of dissimilar materials are continuously increasing to realize multifunctional chips on a single platform. So far, heterointegration of single-crystalline materials has been carried out either by monolithic approaches using heteroepitaxy or by transfer of semiconductor membranes from foreign substrates. For heteroepitaxy, elemental semiconductors such as Si and Ge have been widely utilized as epitaxial templates for growing compound semiconductors owing to their substantially lower costs and compatibility with mature platforms. However, heteroepitaxy cannot avoid the formation of crystalline defects such as dislocations and antiphase boundaries (APBs), which severely deteriorate the device performance[4]. Although various approaches have been proposed to mitigate this issue, such as employing metamorphic buffer layers or dislocation filtering structures, these methods cannot completely eliminate such epitaxial defects[5].

On the other hand, layer transfer techniques can be employed to intergrate dissimilar materials without being restricted to lattice-matching requirements[3,6]. For this, active device layers are

chemically, mechanically or optically released from the substrate and stacked onto a foreign substrate of interest. However, the applicability of these methods is limited by many technical challenges, such as poor controllability, low throughput, and damage to the substrate[7,8,9,10,11]. Recently, a 2D material-based layer transfer (2DLT) technique combined with remote epitaxy has been introduced as a promising method to overcome these issues[12–14]. Remote epitaxy allows direct growth on graphene-coated wafers[15], and the epitaxial layers on graphene can be exfoliated off of the substrate instantaneously and precisely from the weak graphene interface[16,17]. Despite such advantages, remote epitaxy can be accomplished only for compound semiconductors[15], and thus, cheap elemental materials such as Si and Ge cannot be utilized as epitaxial layers or growth templates in remote epitaxy[18].

Here, we demonstrate a universal solution that can substantially reduce crystallographic defects in heteroepitaxial layers while allowing fast mechanical layer release. This is realized by an epitaxy on nanopatterned graphene (EPG) technique, where we perform lateral overgrowth on wafers coated with patterned graphene. The EPG technique provides the following unique features: i) epilayers can be readily released off of the wafer by simple mechanical exfoliation by reduced interface toughness with graphene nanopatterns, ii) elemental materials can not only be utilized as substrates but be made as freestanding membranes due to selective nucleation, iii) APB-free growth of compound semiconductors is permitted on elemental semiconductor substrates due to the blockage of step edges by graphene, and iv) dislocations can be substantially reduced in lattice-mismatched heteroepitaxy due to lateral relaxation by the flexibility and chemical inertness of graphene.

Fig. 1a shows schematics of the process flow for epitaxy on graphene nanopatterns and release of the epilayers. We first utilize graphene-coated Ge(100) substrates as a growth template, on which Ge and GaAs (that are lattice-matched) are grown through graphene stripes. Graphene is first grown on an on-axis Ge substrate, followed by lithography and dry etching (see Methods and Supplementary Fig. S1,S2 for detailed processes). The growth of Ge and GaAs on GaAs wafers through patterned graphene is also studied. The scanning electron microscopy (SEM) images in Fig. 1b show that Ge and GaAs films grown by metal-organic chemical vapor deposition (MOCVD) are fully planarized after growing a nominally 1 μm-thick film (detailed growth processes in Methods). The electron backscatter diffraction (EBSD) maps and X-ray diffraction (XRD) characterizations reveal that the entire film is single-crystalline (Fig. 1b and Supplementary Fig. S3), due to the selectivity for the exposed region over the graphene-coated region (see the density of nuclei in Supplementary Fig. S4).

The mergence and planarization of the film from the patterns are governed by the pattern geometry and crystal orientation-dependent growth rates (see Supplementary Fig. S5)[19].

We developed analytical solutions from conventional spalling theory to estimate the criteria for exfoliation at graphene interfaces. In principle, the generation and propagation of cracks through a medium are governed by stress intensity factors, $K_I$ (opening mode) and $K_{II}$ (shear mode), exerted by the stressor layer, and fracture toughness $K_{IC}$ of the spalled medium[20] (see Supplementary Section 1 for detailed theory). When graphene nanopatterns are introduced, the presence of graphene effectively weakens the interface because the bonding strength of graphene-covered surface is marginal[21,22]. For a graphene coverage percentage of $x$, the *effective* fracture toughness at the interface becomes,

$$K_{IC,eff} = (1-x)\, K_{IC} ,$$

and, as the thickness of the epilayer deviates from the spalling depth ($K_{II} \neq 0$), the condition for spalling changes to,

$$K_I^2 + K_{II}^2 > K_{IC}^2 .$$

On the other hand, the delamination of a stressor layer from the surface of the epilayer occurs when the energy release rate provided by the stressor is not sufficient for crack propagation, expressed as,

$$K_I < K_{IC.eff} ,$$

and outside these spalling and delamination regimes, exfoliation occurs at the graphene interface (see Supplementary Section 1 and Supplementary Figs. S6-S9 for more discussion).

The exfoliation criteria we developed (Fig. 1c and 1d) agree well with our experimental results. As shown in the photograph and SEM images in Figs. 1e,f and Supplementary Figs. S10,S11, the entire area of the 1 μm-thick epilayer can be exfoliated off of the wafer, determined by the plots in Figs. 1c and 1d. The surface morphology of the substrate following exfoliation is flat on the graphene-covered regions, while exposed regions show undulation with a height fluctuation of tens of nanometers (Fig. 1g and Supplementary Fig. S12). When the accumulated strain energy within the Ni stressor layer is high ($K_I^2 + K_{II}^2 > K_{IC}^2$), the substrate spalls and reveals its zig-zag {110} cleavage planes of GaAs and a relatively planar (100) plane for Ge, as shown in Fig. 1h and Supplementary Fig. S11c[20,21]. On the other hand, when the stress is too low ($K_I < K_{IC.eff}$), then cracks cannot propagate, resulting in the delamination of the Ni layer or the handling tape, as shown in Fig. 1i. The same principle can be applied to produce freestanding membranes for different materials as well

(Supplementary Fig. S13). This is in contrast to the conventional controlled spalling method, wherein the spalling depth cannot be reliably controlled and the spalled surface is roughened[7,8].

We also show that the EPG technique can eliminate the formation of APBs in III-V epilayers. The formation of APBs is unavoidable in conventional III-V epitaxy on elemental substrates of on-axis (100) orientation due to the presence of monoatomic steps on the surface[23]. Thus, APBs are clearly observed when GaAs is directly grown on Ge(100), as shown in Fig. 2a. However, our EPG shows complete elimination of APBs when the alignment of graphene stripes is along <110> directions of Ge surfaces. As shown in Figs. 1b and 2b, the GaAs film grown on graphene stripes aligned to <110> directions exhibits no APB. The enhancement of crystal quality by APB elimination is also confirmed by XRD characterizations (Supplementary Figure S14). Interestingly, APBs still appear for GaAs on graphene patterned along <100> directions (Supplementary Fig. S15). We speculate that this is because step edges tend to form along <110> directions due to surface reconstruction,[24] and such <110> steps can be periodically covered by graphene patterns along the <110> directions. In order for APBs to form from graphene nanopatterns, more than two step edges need to co-exist on the exposed region between two graphene stripes, which is unlikely to occur in our pattern dimensions[25].

The impact of APB elimination is confirmed by comparing optoelectronic and electronic performances of III-V devices. AlGaAs-based red light-emitting diodes (LEDs) grown on patterned graphene are APB-free while those directly grown on Ge exhibit APBs in its microstructures (Figs. 2c,d). When we fabricated these LED devices (see Methods for details), we observed a higher reverse-bias dark current and a higher forward-bias recombination current for LEDs with APBs directly grown on Ge (Fig. 2f), substantiating the superior material quality of APB-free LEDs grown on patterned graphene. This is also substantiated by electroluminescence (EL) measurements, which indicate a significantly brighter EL and efficient current spreading in LEDs grown on patterned graphene when compared with LEDs without graphene (Figs. 2g-i).

We next show the defect reduction and strain relaxation in lattice-mismatched heteroepitaxial systems, which is conducted by theoretically and experimentally comparing heteroepitaxy on patterned graphene with direct heteroepitaxy and $SiO_2$ mask-based conventional selective-area epitaxy. In three-dimensional molecular dynamics (MD) simulation models, we studied the epitaxy of Ge on Si(100) as a representative case of ~4 % lattice-mismatched systems. Three cases are investigated: direct epitaxy without masks, epitaxy with thin and flexible masks (analogous to graphene), and epitaxy with thick and rigid masks (analogous to $SiO_2$) (see Methods for detailed MD

simulations setup). Fig. 3a shows the direct heteroepitaxy case without masks, in which multiple misfit and threading dislocations are formed due to the substantial lattice mismatch, along with stacking faults. In the presence of flexible monolayer graphene masks, the formation of dislocations and stacking faults is effectively suppressed (Fig. 3b). Deformation of graphene is clearly observed by laterally accommodating the misfit strain. On the other hand, as shown in Fig. 3c, rigid patterns exhibit strain buildup at the edges of the mask as it cannot dynamically accommodate misfit strain at the edges, resulting in misfit dislocations, threading dislocations, and stacking faults (see also Supplementary Fig. S16).

Experimentally, we study heteroepitaxy of InAs on InP substrates with 3.2% lattice-mismatch as a model system. Heteroepitaxy is performed on both monolayer graphene and 30-nm-thick $SiO_2$ masks with the same mask width and periodicity. Compared to the case of direct growth of 1 μm-thick InAs on InP, a substantial reduction of dislocations is observed for 1 μm-thick InAs grown on graphene patterns as shown in the scanning transmission electron microscopy (STEM) images in Figs. 3d and 3f. Geometrical phase analysis (GPA) at the interfaces shows that the lattice near the interface is significantly distorted in direct heteroepitaxy (Fig. 3e), whereas the strain is mostly relaxed near the edge of graphene (Fig. 3g). The high-resolution STEM image and GPA maps in Fig. 3g and Supplementary Fig. S17 clearly show slight bending of graphene near the edge and complete relaxation of strain in the film above graphene, which substantiates the graphene's unique effect on dislocation reduction by its bendability and chemical inertness[26,27]. On the other hand, $SiO_2$ patterns are less effective than graphene patterns in dislocation reduction (Fig. 3h) as predicted by our simulations. The epilayer is only slightly relaxed near the edges of the $SiO_2$ mask (Fig. 3i) due to the rigidity and thickness of $SiO_2$, inducing localized strain (denoted by an arrow in Supplementary Fig. S17). Therefore, these findings clarify that the deformable and slippery nature of graphene provides an additional path for strain relaxation and enables reduction of dislocations, whereas nucleation and threading of new dislocations are observed at the edges of the $SiO_2$ masks. It should be noted that effective elimination of APBs by the EPG technique has also been confirmed for lattice-mismatched heteroepitaxy system such as InGaAs on graphene-coated Ge substrates (see Supplementary Fig. S18). In addition, heteroepitaxial films on the patterned graphene are successfully released from the substrates as in the case of GaAs and Ge material systems.

We note that air voids are occasionally formed during lateral overgrowth on graphene or $SiO_2$ masks, as shown in the cross-sectional STEM images in Figs. 2a, 3f, 3h, and Supplementary Fig. S19, S20. This phenomenon is well-understood in epitaxial lateral overgrowth of III-V materials[28–31], and

the formation of voids can be controlled or eliminated by tuning the mask geometry or growth conditions[29,30,32]. When laterally grown layers are merged, threading dislocations may be generated at the coalescence boundaries[32,33], which is also observed in our EPG approach (Supplementary Fig. S19). Although such threading dislocations initiated at coalescence boundaries adversely affect the overall crystal quality of epilayers, we emphasize here that the overall crystal quality is improved by the EPG technique due to the roles of graphene revealed above.

The impact of EPG technique on highly mismatched systems is studied by growing InAs on GaAs substrates, exhibiting 7.2% lattice-mismatch, with graphene patterns having various pitches and opening widths. As shown in the electron-channeling contrast images (ECCI) of InAs epilayers of the same thicknesses of 1 μm (see Fig. 4a and Supplementary Fig. S21), dislocation density is progressively reduced on the surface as the graphene coverage increases. Monotonic decrease of dislocation density is observed by plotting the density as the function of the graphene coverage from 0% to 92%. This proves that the impact of graphene coverage is substantial as it shows an order of magnitude reduction of dislocations by simply varying the coverage (Fig. 4b). MD simulations also predict a reduction of dislocations and stacking faults by increased graphene coverage as shown in Fig. 4c and Supplementary Fig. S22, in agreement with experimental results. It should be highlighted that this technique provides unique solutions for obtaining heteroepitaxial films with significantly reduced dislocation densities that can be mechanically released from the substrate.

In conclusion, we demonstrate graphene nanopatterns as a universal platform for the epitaxy of single-crystal films, where both elemental and compound semiconductors can be used for the substrates as well as the epilayers. The three modes of peeling – spalling, exfoliation, and delamination – are theoretically proposed and experimentally demonstrated, proving that the grown films can be readily exfoliated with good controllability regardless of the film thickness due to the weak interfaces intentionally formed by graphene stripes. Moreover, APBs completely disappear when III-V films are grown on elemental substrates with graphene stripes, resulting in high-quality optoelectronics III-V devices that can be made freestanding and transferred onto foreign platforms for heterointegration. Our theoretical analysis of dislocation reduction by the dangling-bond-free and ultrathin graphene in lattice-mismatched heteroepitaxy supports the experimental results. Overall, we provide a new pathway for the production of various high-quality and single-crystal membranes, overcoming polarity and lattice-matching constraints which have been a critical obstacle for heterointegrated multifunctional systems.

## Acknowledgments

The team at MIT acknowledges support by the Defense Advanced Research Projects Agency Young Faculty Award (award no. 029584-00001), the Air Force Research Laboratory (award no. FA9453-18-2-0017 and FA9453-21-C-0717), the U.S. Department of Energy's Office of Energy Efficiency and Renewable Energy (EERE) under the Solar Energy Technologies Office (Award No. DE-EE0008558), and Universiti Tenaga Nasional and UNTEN R&D Sdn. Bhd., Malaysia through TNB Seed fund grant no. U-TV-RD-20-10. STEM was performed at the Center for Electron Microscopy and Analysis (CEMAS) at The Ohio State University. M.Z and J.H acknowledge support by the National Science Foundation under NSF Award Number DMR-2011876.

## Author contributions

J.K. and S.H.B. conceived the idea. H.K., S.L. and J.S. designed and coordinated the experiments. M.A., Y.Z. and Y.S. conducted theoretical studies and simulations of epitaxy. Epitaxial growth was performed by H.K., K.Lu., and Y.B. Graphene growth and transfer were performed by H.K., S.L., K.Lu., N.M.H., K.S.K., H.S., H.S.K., S.-I.K., J.-H.L. and J.-H.A. Patterning, exfoliation and device fabrication were performed by S.L., J.S., H.K., K.Lu., B.-I.P., C.C., H.Y., Y.M., and S.S. Exfoliation theory is developed by H.K., S.L., N.M.H., K.Lee., S.-H.B. and J.K. STEM measurements and GPA analysis were conducted by M.Z. and J.H. Material characterizations were conducted by H.K., S.L., N.M.H., K.Lu., C.S.C., J.M.S., H.Y., Y.M., and S.S. Optoelectronic characterizations were conducted by H.K. and J.S. The manuscript was written by H.K., Y.S., and J.K. with input from all authors. All authors contributed to the analysis and discussion of the results leading to the manuscript.

## Competing interests

The authors declare no competing interests.

**Fig. 1 | Graphene nanopattern for single-crystal membrane growth and release. a**, Schematic of epitaxy on nanopatterned graphene and layer release. **b**, Plan-view SEM images (left) and EBSD maps (right) of GaAs and Ge grown on GaAs and Ge substrates, showing planarized single-crystalline thin films. Scale bars, 2 μm. **c**, Three modes of peeling as a function of the stressor thickness and epilayer thickness at the Ni stress level of 600 MPa and graphene coverage of 70 % on Ge substrate. The dashed line represents natural spalling depth without graphene (blue line). **d**, Effect of graphene coverage on the peeling modes at the stressor stress of 600 MPa and epilayer thickness of 1 μm. **e**, Photograph of an exfoliated GaAs film (left) and remaining 2-inch Ge wafer (right). **f**,**g**, Plan-view SEM images (**f**) and AFM image (**g**) of the substrate after the peeling. **h**, Plan-view SEM image of GaAs substrate in the spalling regime. **i**, Plan-view SEM images of sample surfaces in delamination regime, showing delamination at the Ni/epilayer interface (left) and tape/Ni interface (right).

**Fig. 2 | APB elimination by graphene nanopatterns. a**,**b**, Cross-sectional STEM images of GaAs grown directly on Ge (**a**) and on nanopatterned graphene-coated Ge (**b**). **c**,**d**, Plan-view SEM images of AlGaAs red LEDs grown on bare Ge (**c**) and on nanopatterned graphene-coated Ge (**d**). **e**, Cross-sectional SEM image of LED fabricated by exfoliating the LED structure from the substrate and transferring onto polyimide/silicon substrate. **f**, I-V curves of fabricated LEDs on Ge with and without nanopatterned graphene. Error bars represent standard deviation after log transformation. **g**, Comparison of EL spectra of LEDs on Ge without (left) and with (right) nanopatterned graphene under various injection currents. **h**,**i**, Microscopic photographs of EL from red LEDs with different sizes and geometries on nanopatterned graphene-coated Ge (**h**) and on bare Ge (**i**). Injection currents, 3 mA, 3 mA, 5 mA, and 7 mA (from left to right). Scale bars, 10 μm.

**Fig. 3 | Defect reduction in lattice-mismatched heteroepitaxy by graphene nanopatterns.** MD simulations of heteroepitaxy **a**, without graphene, **b**, on thin and flexible graphene mask, and **c**, on thick and rigid mask. Dislocations are colored according to their Burgers vector: blue for 1/2<110>, green for 1/6<112>, purple for 1/6<110>, and cyan for 1/3<111>. Atoms are colored as blue and transparent for perfect diamond cubic structure, orange and opaque for stacking faults. Carbon atoms are colored gray, and epilayer/substrate interfaces are indicated as dashed lines. **d**, Low-magnification STEM image of InAs grown directly on InP without a mask, and **e**, high-resolution STEM image (left) and corresponding GPA maps showing in-plane (center) and out-of-plane (right) strain. **f**, Low-magnification STEM image of InAs grown on graphene pattern, and **g**, high-resolution STEM image and corresponding GPA maps at the edge of graphene, showing relaxed InAs film with slightly deformed graphene. **h,i,** Same set of data for InAs grown on $SiO_2$ pattern, showing severe strain at the interface and at the mask edge. Enlarged atomic-resolution STEM image of **i** is in Supplementary Fig. S23.

277 **Fig. 4 | Effect of graphene coverage. a**, ECCI images of InAs grown on nanopatterned graphene-
278 coated GaAs with different graphene coverages. Scale bars, 200 nm. **b**, Surface dislocation density as
279 a function of graphene coverage measured by ECCI. **c**, MD simulations of heteroepitaxy of Ge on
280 Si(100) with different mask widths covering 0%, 20%, and 40% of the surface, showing a decrease
281 of defects by increased graphene coverage. The color coding is the same as Fig. 3.

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## Methods

**Graphene formation.** For Ge substrates, graphene is grown directly on Ge(100) by CVD (TCVD-50B, Graphene Square Inc.) at atmospheric pressure. Ge(100) wafers are first cleaned in a diluted HCl solution (10% HCl in water) for 3 minutes, followed by water rinsing and nitrogen blow-drying. After loading Ge substrates into the CVD system, the CVD tube is first purged with Ar for 30 minutes at room temperature, followed by ramping the temperature up to 910 °C which takes 30 minutes. At 910 °C, graphene is grown by flowing $H_2$ of 730 sccm and $CH_4$ of 200 sccm for 60 minutes. After the growth, the tube is cooled down to room temperature by flowing Ar of 140 sccm. The graphene thickness obtained is between mono- to bilayer.

For III-V substrates, graphene is first formed on a copper foil by CVD, followed by a standard wet transfer process to transfer the graphene onto III-V. The details on the graphene growth and transfer can be found in ref.23. GaAs substrates are deoxidized by a diluted HCl, and InP substrates by a 5:1 buffered oxide etchant (BOE; J.T.Baker, USA), and both are cleaned with water right before scooping the graphene. Because remote epitaxy of III-V requires dry-transferred graphene and does not work on wet-transferred graphene due to interfacial oxidation, employing wet-transferred graphene in this study ensures that the growth of single-crystalline membranes is the result of a purely lateral overgrowth, not by a mixed growth mode with a portion of remote epitaxy[34].

**Graphene patterning.** After the graphene formation, graphene is patterned at nanoscale by various types of lithographic methods, including e-beam lithography, interference lithography, and stepper lithography. E-beam lithography technique is mainly used to study the epitaxial film growth and exfoliation behavior depending on the pattern geometries. 200 nm-thick polymethyl methacrylate (PMMA) resist layer is spin-coated on graphene and baked at 180 °C for 2 min, followed by exposure using Elionix ELS-F125 e-beam lithography system. Exposed samples are then developed in methyl isobutyl ketone (MIBK):isopropanol (IPA) = 1:3 for 60 s and washed out in pure IPA. Developed PMMA patterns are transferred to graphene by reactive ion etching (RIE) via Plasma-Therm 790 with $O_2$ (20 s, 6 mTorr, 90 W), followed by rinsing overlying PMMA layer in acetone to finish graphene patterning process. For large-area thin film growths and LED device fabrication, interference lithography or stepper lithography is employed to produce millimeter- to centimeter-scale patterns. Nanoscale gratings are interferometrically or photolithographically patterned utilizing the interference pattern of 325 nm HeCd laser generated by the Lloyds-mirror lithographic system or exposing in GCA

AS200 i-line Stepper, respectively. For both processes, 100 nm-thick positive photoresist (Futurrex PR1-100A1) is first spin-coated on graphene and baked at 120 °C for 2 min. After exposure, the samples are developed in Futurrex RD6 diluted at 3:1 with deionized (DI) water for 15 s and rinsed in pure DI water. The rest of the process is the same as e-beam lithography.

**Epitaxy.** Ge, GaAs, and InAs epitaxy are conducted in a close-coupled showerhead MOCVD reactor using arsine, trimethylgallium, trimethylaluminum, trimethylindium, and germane as sources of As, Ga, Al, In, and Ge, respectively. Disilane and dimethylzinc are used as Si and Zn dopants, respectively. The reactor pressure is kept at 100 Torr during the growth, and nitrogen is used as a carrier gas. Ge growth is conducted at 650 °C with a growth rate of ~30 nm/min. GaAs growth is conducted at 650 °C with a growth rate of ~33 nm/min and a V/III flow rate ratio of ~45. InAs growth is conducted at 650 °C with a growth rate of ~23 nm/min and a V/III flow rate ratio of ~65. For the growth on GaAs and InP substrates, arsine and phosphine are respectively flown during the temperature ramp-up from 300 °C to the growth temperature to prevent substrate desorption before the growth. Similarly, after the growth of GaAs and InAs films, arsine is flown during the temperature ramp-down to 300 °C. For the growth of red LED structures, a 2 μm-thick GaAs buffer is first grown at 650 °C, followed by a 700 nm-thick p-GaAs bottom contact layer, 350 nm-thick p-$Al_{0.65}Ga_{0.35}As$ barrier, 300 nm-thick $Al_{0.35}Ga_{0.65}As$ emitter, 350 nm-thick n-$Al_{0.65}Ga_{0.35}As$ barrier, and 100 nm-thick n-GaAs top contact layer at 700 °C. Although p-GaAs is more commonly used as a top contact layer, we employed n-GaAs as a thin top contact layer and p-GaAs as a thick bottom contact layer because we did not employ an additional current spreading scheme and both holes and electrons are laterally injected.

**2DLT and device fabrication.** The grown films are exfoliated by first depositing a 30 nm-thick Ti adhesion layer by e-beam evaporation, with a deposition rate of ~0.1 nm/sec. Next, a Ni stressor layer is deposited by direct current (DC) sputtering in the same chamber with a DC power of 500 W and a constant Ar flow of 6 sccm. The stress level of Ni is controlled by the chamber pressure during the sputtering, which typically ranged around 1.1-1.8 mTorr, with a higher pressure resulting in a higher stress level. After the deposition of metal, a thermally releasable tape (TRT; Revalpha, release temperature ~150 °C; Semiconductor Equipment Corp., USA) is attached to the metal by gently rubbing with a cotton swab. The tape edge is then lifted up by holding with a tweezer, which initiates cracks from the sample edge. The cracks propagate as the tape is further lifted up, and the mechanical exfoliation finishes when the entire TRT/stressor/epilayer stack is detached from the substrate.

Exfoliated AlGaAs LED layer on TRT is transferred on a Si wafer by treating with oxygen plasma (Anatech Barrel Plasma System), spin-coating 1 vol% aqueous solution of (3-

Aminopropyl)triethoxysilane (APTES; Sigma-Aldrich, USA) at a speed of 3000 rpm for 30 seconds, and baking at 110 °C for 1 minute on both LED and receiver substrate surfaces. The substrate is subsequently spin-coated with polyimide precursor (PI-2545; HD Microsystems, USA) at a speed of 3000 rpm for 30 seconds, baked at 110 °C for 30 seconds, bonded with the LED film on TRT and pressed in steel vise (Toomaker's vise; Tormach, Inc., USA), and baked further at 180 °C for 10 minutes before TRT is removed. Final curing in a 250 °C convection oven completed the transfer process. Wet etching in $FeCl_3$ solution (MG Chemicals, Canada) and in 5:1 BOE removed Ti/Ni layers.

LED mesa structures are fabricated by photolithography and reactive ion etching (RIE; PlasmaPro 100 Cobra 300 System; Oxford Instruments, UK) in $Cl_2$ gas. Both the top and bottom metal contact pads are formed by photolithography, electron-beam evaporation of Cr/Au (~15/100 nm), and metal lift-off.

**Characterizations.** Cross-sectional STEM specimens were prepared with conventional focused ion beam lift-out technique using Helios NanoLab 600. Argon ion milling under 900 and 500 eV was used to clean the surface amorphous layer and minimize subsurface damage. STEM images were collected using a probe-aberration corrected Thermo Fisher Scientific Themis Z S/TEM operated at 300 kV, 20 mrad convergence semi-angle. Strain mapping of the film with respect to the substrate was conducted using GPA[35] based on atomic resolution images.

Atomic force microscopy (AFM) measurements were conducted using an AFM probe with a silicon tip (PPP-NCHR, Nanosensors) by noncontact mode (Park NX10, Park Systems).

SEM and EBSD characterizations were conducted using a Zeiss Merlin high-resolution SEM system. SEM images were measured using a beam acceleration voltage of 3 kV and a current of 0.1 nA, and EBSD maps were measured using an EBSD detector with a beam acceleration voltage of 15 kV and a current of 3 nA.

Raman and EL spectra were measured using a Renishaw Invia Reflex Micro Raman system with a CCD detector, and I-V characteristics were measured using a Signatone Probe Station (Signatone Corp., USA) equipped with a semiconductor parameter analyzer (Agilent 4156C; Keysight Technologies, USA) and a camera system connected with an optical microscope for collecting images.

**Molecular dynamics simulations.** MD simulations were carried out via LAMMPs[36,37] package with equations of motion integrated using the velocity-Verlet algorithm under a time step of 1 fs. To mimic the behavior of Ge-Si systems, Stillinger–Weber potential parameterized by Ethier[38] was employed. The interaction of carbon atoms within a graphene layer is also described by Stillinger–Weber

potential, parameterized by Bourque *et al.*[39]. The interaction between graphene and Si-Ge is hard-sphere only for simplicity since the weak vdW attraction is negligible at high temperatures. For convenience, C-Si and C-Ge interactions are also modeled using the Stillinger-Weber formulation with only the two-body term (effectively a tailed Lennard-Jones 12-6 potential) with the following identical parameter: $\varepsilon = 0.04\,eV$, $\sigma = 0.35\,nm$, $p = 12$, $q = 6$, $a = 1.12$, $A = 1$, and $B = 1$. Our molecular dynamic simulations consist of a 1.2-nm-thick Si(100) substrate with the cross-section dimensions of 20.2 ($x$) by 6.0 ($y$) nm$^2$. To mimic the rigid $SiO_2$ mask, multiple layers of graphene are introduced without permitting the carbon atoms to move. The simulation box in the $z$-direction is 43.6 nm. The lattice constant of Si was chosen to be 0.545 nm (lattice constant at the growth temperature used here). The bottom layer of Si substrate was fixed. The growth temperature was set to 2100 K in order to facilitate the diamond cubic structure formation under the extremely high deposition rate, which is typical for MD simulations. Lower growth temperature leads to significant amorphous Ge film formation. Si and Ge crystals are stable under this temperature as shown in the animations, which is attributed to the deficiency of the potential used here[38]. The temperature is controlled using Nose–Hoover thermostat[40]. We note that the Ge/Si/C system instead of the experimentally-employed In/As/P/C system can eliminate the complexity such as non-stoichiometry, while still effectively representing lattice-mismatched epitaxy environments with graphene nanopatterns. To model the flexible graphene mask, there is an external force of 0.015 eV/Å applied on each carbon atom (excluding about 1 nm width on both edges) towards the Si substrate to prevent the graphene mask from leaving the substrate. Ge atoms are introduced randomly at the top of the simulation box periodically with a downward velocity. For all the MD simulations presented here, the growth rates are identical, which is roughly 0.1 nm/ns. Periodic boundary conditions (PBC) were applied in all three directions of the simulation box. Therefore, both the flexible mask and rigid mask represent infinitely long stripes with equal spacing on the silicon substrate. A wall was imposed on the top of the simulation box to prevent atoms from depositing to the backside of the substrate. The interaction is a 9-3 Lennard-Jones potential ($\varepsilon = 0.01\,eV$, $\sigma = 0.1\,nm$, $\sigma_{cutoff} = 0.25\,nm$). OVITO visualization software[41] was used to generate simulation snapshots.

**Data availability**

The data that support the findings of this study are available from the corresponding author upon reasonable request.

## Methods-only references


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